

Stack Gas Emission Monitoring

ECM is providing stack gas monitoring systems based on all currently available architectures:

- Straight extraction
- Dilution
- In-situ

Gas monitoring equipment is based on proven techniques:

- NDIR
- UV absorption
- UV fluorescence
- Chemiluminiscence
- FTIR
- Tuneable laser diodes
- FID Chromatography

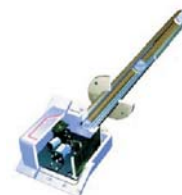


For particle monitoring following certified methods are applied:

- Optical instruments
- Electrodynamic monitors

Flow monitors are based on following methods:

- Ultrasonic
- Anubaric
- Discontinuity

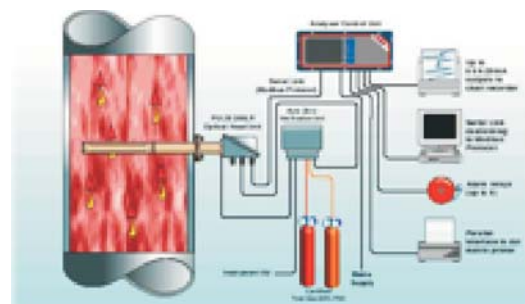


For continuous emission monitoring systems usually monitored compounds are:

- | | | | |
|---------------------------------|-------------------|---------------|--------------------|
| ▶ SO ₂ | ▶ HCl | ▶ Particles | ▶ H ₂ S |
| ▶ NO _x | ▶ HF | ▶ Flow | ▶ TRS |
| ▶ CO | ▶ NH ₃ | ▶ Pressure | ▶ CO ₂ |
| ▶ C _x H _y | ▶ O ₂ | ▶ Temperature | |

ECM is offering several solutions for analysis of gaseous pollutants based on extractive or in-situ instrumentation.

Advantage of in-situ instrumentation is simplicity of installation and resistance against corrosive compounds.



ECM ECO Monitoring

Environmental & Process Monitoring instrumentation & systems

Advantage of extractive methods is high accuracy and possibility to apply advanced methods, such as FTIR, tuneable laser diode or FID based instruments.



Beyond of monitoring of gaseous pollutants, monitoring of particles and auxiliary parameters is also provided.



The data systems are customised for legislation of the respective country and are providing analyser control, calibration check, validation, presentation and archiving of data.

